

Copolymerization of Cyclopropyl-Substituted Dioxolanylmethyl Acrylates with Styrene and Synthesis of Photosensitive Copolymers

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Abstract—Radical copolymerization of new monomers, cyclopropyl-substituted dioxolanylmethyl acrylates, with styrene in benzene solution was studied at low conversions. The copolymer compositions and the relative activity constants and Alfrey–Price constants of cyclopropane-containing dioxolanylmethyl acrylates were determined. The sensitivity of the copolymers obtained to UV radiation was studied, and the possibility of using them as photoresists was revealed.

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